

Atty Docket No. 1771X2T19930

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ATTENTION: Examiner Rudy Zervigon
TELEPHONE NO.: 703-308-0661

Group Art Unit 1763

OFFICIAL COMMUNICATION
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EXAMINER Rudy Zervigon

CERTIFICATION OF FACSIMILE TRANSMISSION

I hereby certify that the following document(s) in re Application of SEBASTIEN RAOUX ,
Application No. 08/988,246, filed December 1, 1997 for METHOD AND APPARATUS FOR
MONITORING AND ADJUSTING CHAMBER IMPEDANCE is being facsimile transmitted to
the Patent and Trademark Office on the date shown below.

Document(s) Attached

1. Supplemental Amendment

Number of pages being transmitted, including this page: 4

Dated: June 20, 2002



Andrea S. Beck
for Chun-Pok Leung, Reg. No. 41,405

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TOWNSEND and TOWNSEND and CREW LLP
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**SUPPLEMENTAL AMENDMENT
UNDER 37 CFR 1.116 EXPEDITED
PROCEDURE - EXAMINING GROUP
1763**

PATENT
Attorney Docket No.: 1771X2T19930
TTC No.: 016301-019930

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

SEBASTIEN RAOUX et al.

Application No.: 08/988,246

Filed: December 1, 1997

For: METHOD AND APPARATUS FOR
MONITORING AND ADJUSTING
CHAMBER IMPEDANCE

Examiner: Rudy Zervigon

Art Unit: 1763

**SUPPLEMENTAL AMENDMENT
UNDER 37 CFR 1.116 EXPEDITED
PROCEDURE EXAMINING GROUP 1763**

Box AF

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Advisory Action dated May 21, 2002 in the above-identified application, please amend the above application as follows:

IN THE CLAIMS:

Please cancel claim 21 and amend claims 3, 13, and 14 as follows.

3. The substrate processing system of claim 11 wherein said processor receives as an input the measured impedance level of said plasma.

13. The substrate processing system of claim 11 further comprising an impedance tuner coupled in series to said substrate holder.

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